

Visualization of Structure and Composition During Photocathode Growth

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Lawrence Berkeley National Lab.

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Brookhaven National Lab.

Brookhaven National Lab/SUNY Stony Brook

SUNY Stony Brook

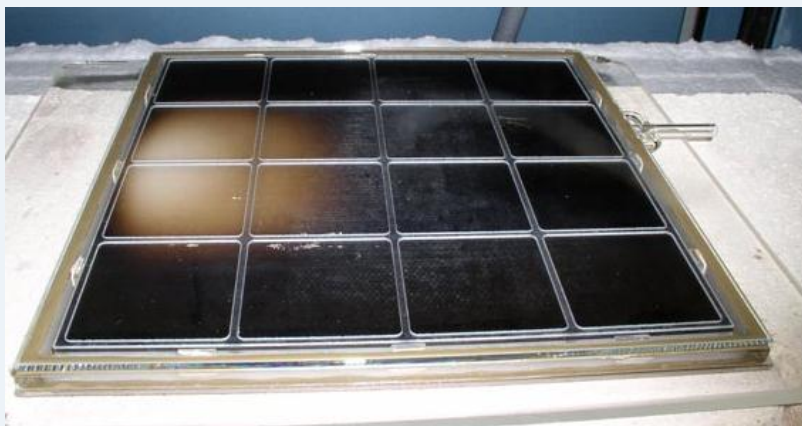
SUNY Stony Brook

Brookhaven National Lab.

BESSY/Helmholtz-Gesellschaft

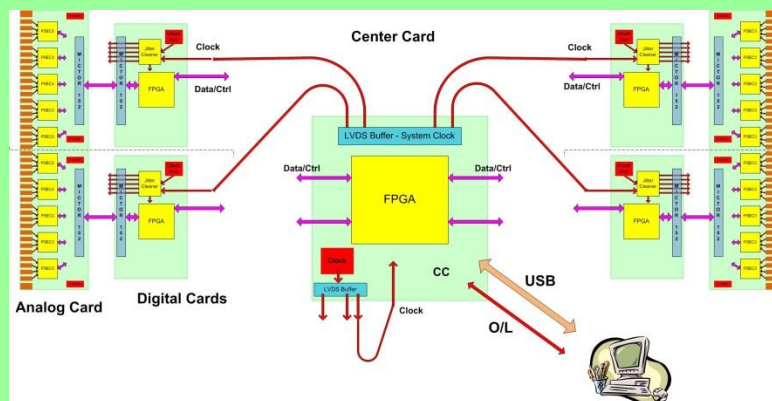
The 4 `Divisions' of LAPPD

Hermetic Packaging



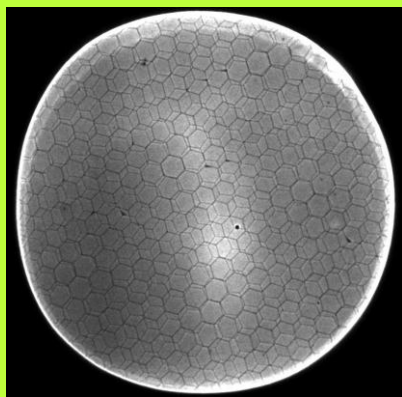
See Bob Wagner's talk

Electronics/Integration



See Henry Frisch's Talk

MicroChannel Plates

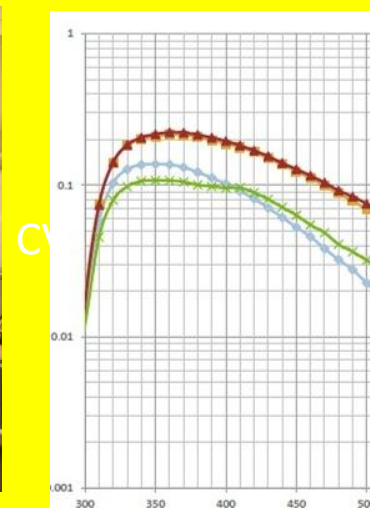


See (hear) Bob Wagner's & Ossy Siegmundtalk

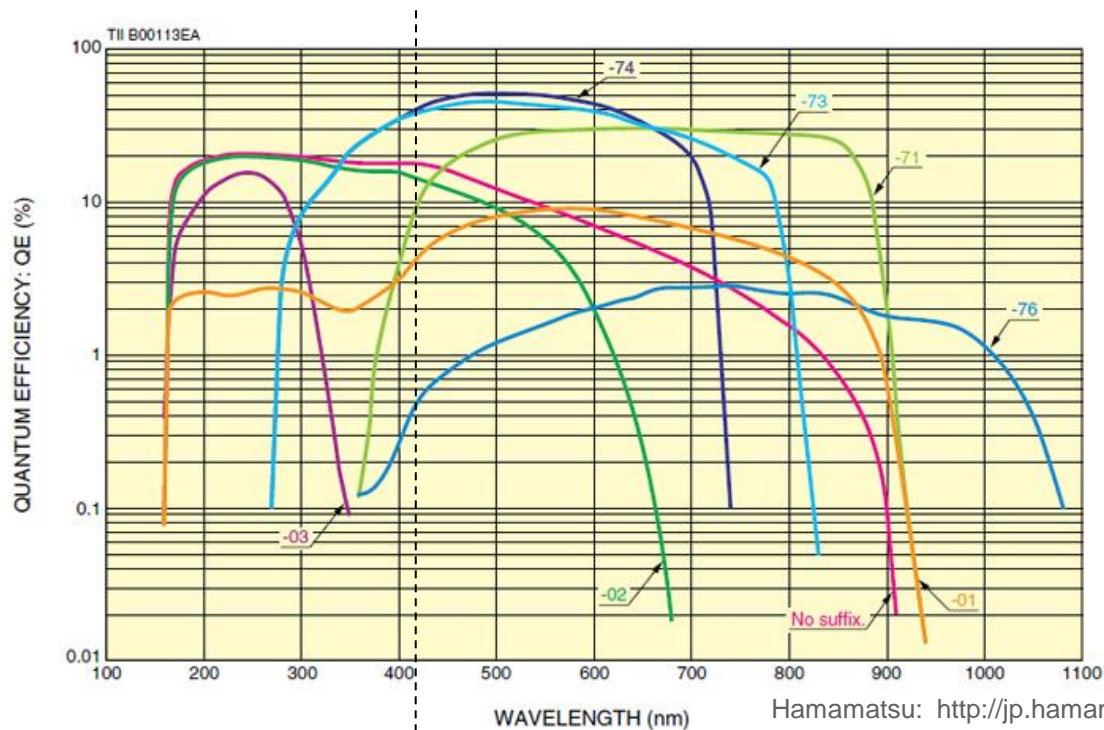
Photocathodes



This Talk



What is a Photocathode?



Suffix	Photocathode	Input Window
-71	GaAs	Borosilicate Glass
-73	Enhanced Red GaAsP	Borosilicate Glass
-74	GaAsP	Borosilicate Glass
-76	InGaAs	Borosilicate Glass
Non	Multialkali	Synthetic Silica
-01	Enhanced Red Multialkali	Synthetic Silica
-02	Bialkali	Synthetic Silica
-03	Cs-Te	Synthetic Silica

- Various cathodes are feasible
 - Only semiconductor cathodes are useful for detection applications
 - Multi-alkali are the the only cathodes available at 400nm and polycrystalline
- Focus on Multi-alkali cathodes:
 - Cost efficient thin film technology
 - Low dark current
 - High conductivity
 - Relative robust (unclear what destroys the cathode)

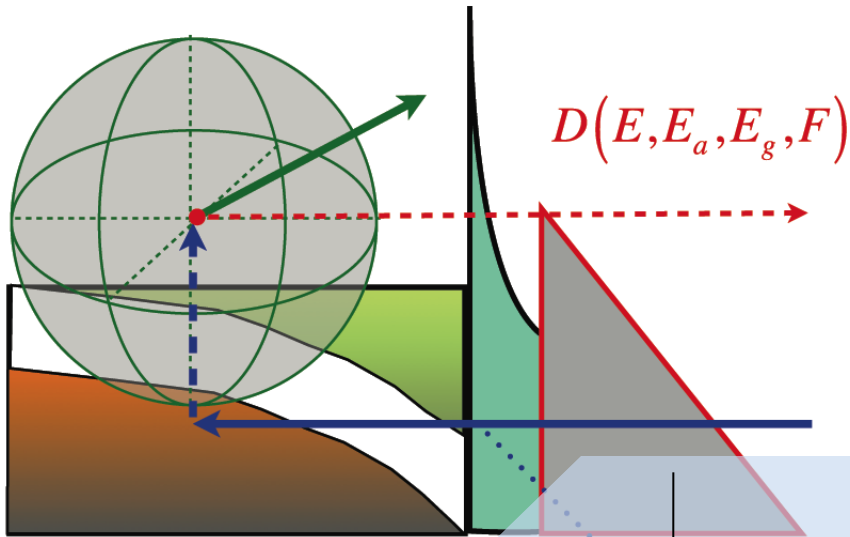
Goals and Activities

- Goals of the project
 - High Quantum Efficiency
 - Unclear what number but larger 50%
 - Response optimized at 400nm
 - First approach: low count rate application
 - High production yield
 - Low variation from batch to batch
 - Independent from “personal experiences” ; can be performed by control system
 - Low production cost
 - Short production cycle
 - Large parameter-acceptance
- Activities:
 - Basic sciences:
 - General understanding and modeling of growth process
 - Pre-selection of optimization parameter space
 - Recipe suggestions
 - Engineering
 - Reproducibility of evaporators
 - Development of process-control parameters
 - Designing process environment for optimized recipe

Basic Sciences

- Visualizing what happens during the growth:
 - Scattering experiments have proven very power full
 - To do:
 - Learning how to analyze data (especially diffuse scattering)
 - Automatic data analysis with automatic creation of rate constants
 - Improving evaporator system to allow “arbitrary” recipe
 - Reconstruction of spatial model
 - Simulation of thin film growth
- What we need from the material:
 - Single crystal in surface normal direction
 - Unclear what is the best lateral size
 - Minimizing impurity scattering (avoiding solid state alloying?)
 - Creating electric fields
 - Substrate effects
 - Doping
 - Layered structures
 - Influence of surface states on dark current

What Determines the Quantum Efficiency?



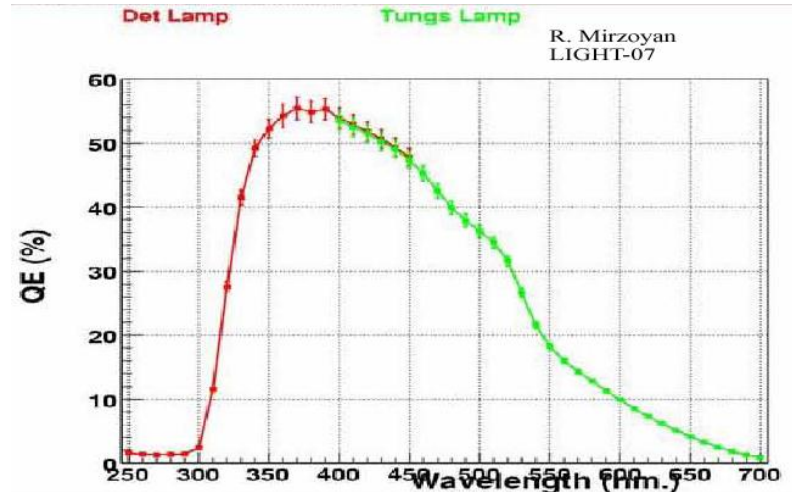
Semiconductor

$$\frac{\hbar^2 k_{\perp}^2}{2m} > E_T = E_f + \phi$$

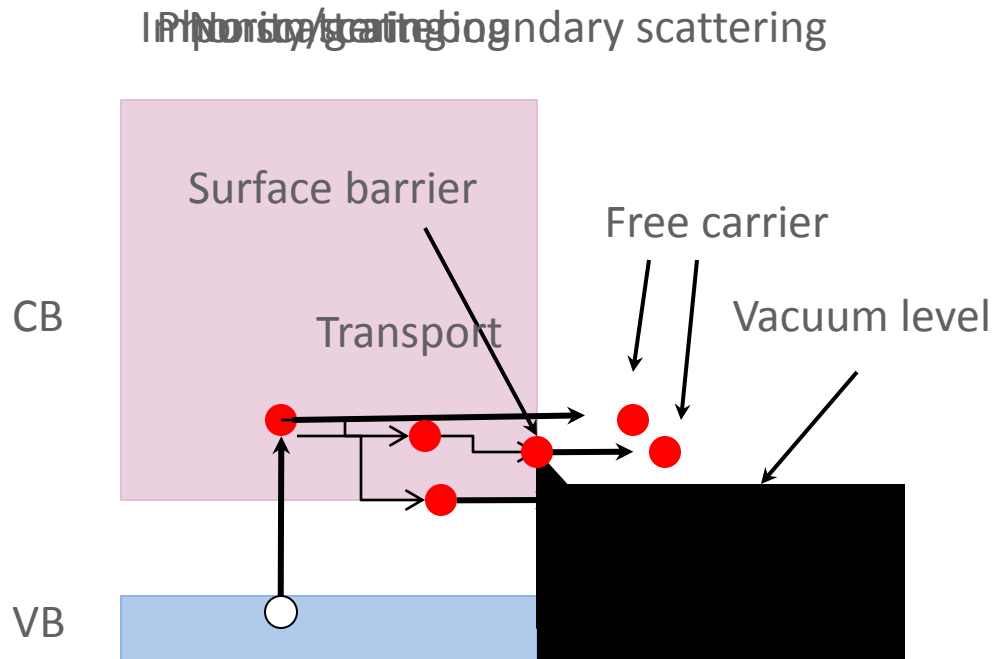
$$QE(\nu) \propto (h\nu - \phi)^2$$

- In perfect Material (multi-alkali)
 - Original photoelectron direction is random (due to s-p character of valence & conduction band).
 - Cone determined by kinetic energy and surface barrier.
 - Phonon scattering helps to increase slightly the escape probability.

Maximal QE ~ 60%?



Why does Materials Quality Play a Role?

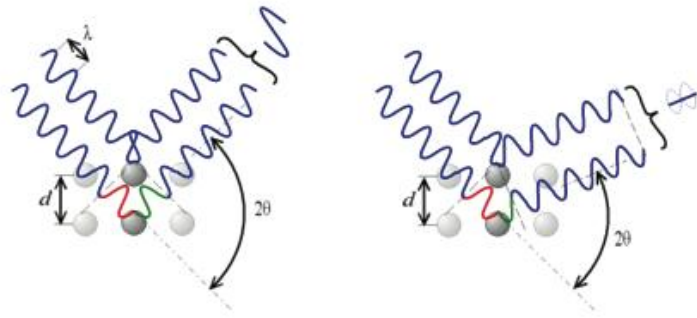


Material composition determines:

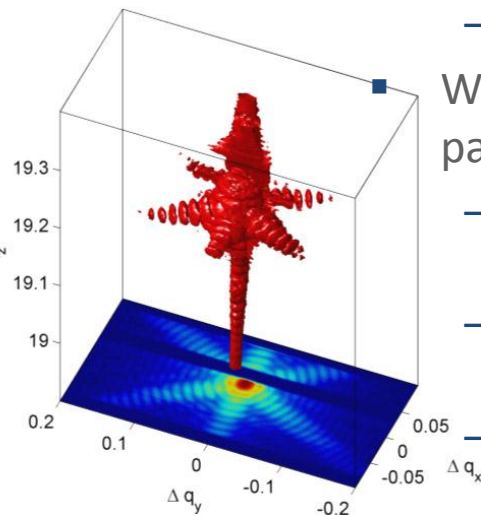
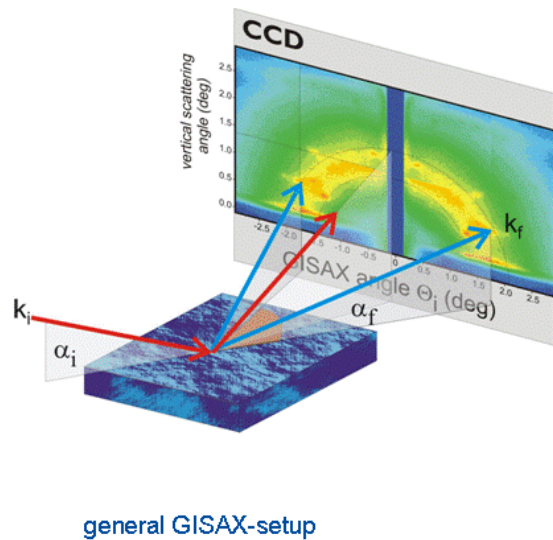
- Band gap
- Work function
- Surface barrier

- Description of cathode functionality in Spicer-Three-Step-Model
 - Absorption, Transport, emission
- No scattering:
 - Photon energy is converted in kinetic energy of photoelectron
 - Electron will be emitted (as long as momentum perpendicular to surface is large enough)
- Phonon scattering
 - Small energy loss per scattering event
 - Randomizing direction
- Impurity/grain boundary scattering
 - Large energy loss per scattering event
 - Small probability to escape!

X-ray Scattering: A Perfect In-Situ Tool to Analyze Composition, Structure, and Chemistry!



- The elementary process
 - Each atom scatters X-rays in 4π
 - An ensemble of atoms:
 - Crystalline form produces “bragg”-peaks
 - Amorphous materials produce a “Pair-Distribution-Pattern”
- Single wavelength diffraction:
 - Single crystal produces typically only one reflection (or none)
 - A powder of single crystals produce Rings

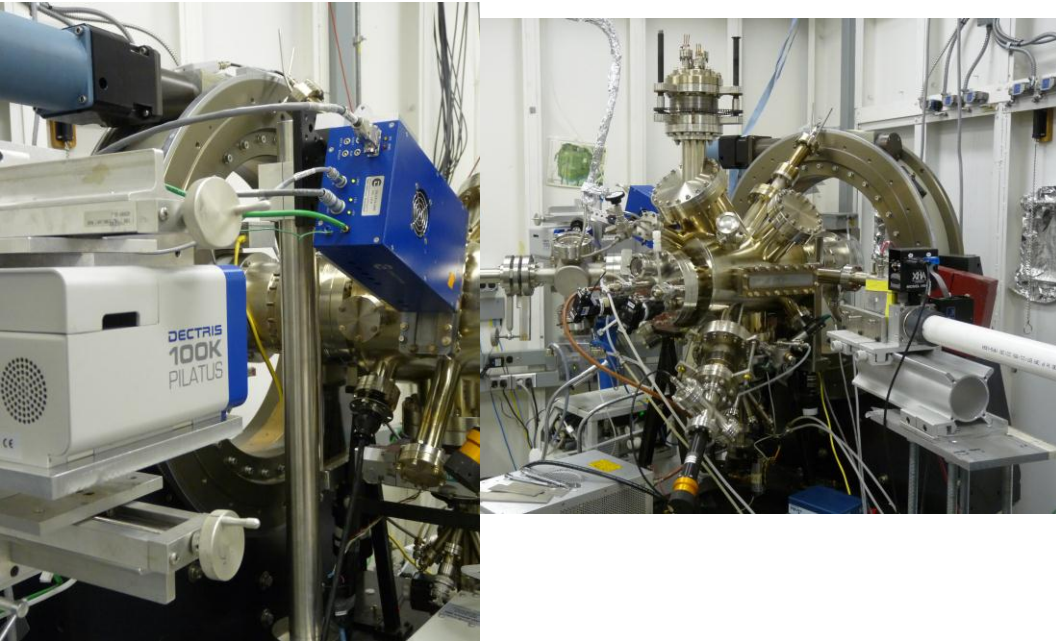


What information is in the diffraction pattern

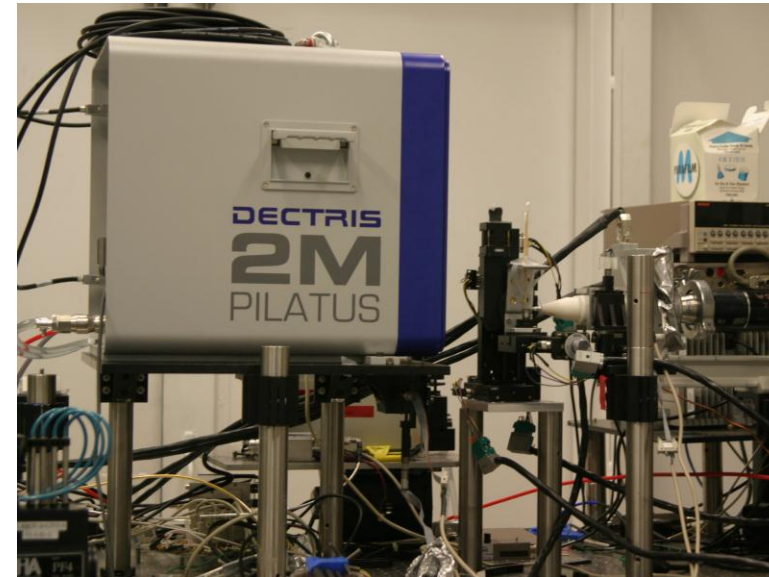
- 2-Theta position is a measure for the lattice-plane distance
- Phi-position reflects orientation of the crystallites
- Width and shape of the reflection reflects crystallite size and/or strain of the crystal
- Detailed analysis of peak-shapes will produce electron-density map of sample

The Experimental Setup

BNL

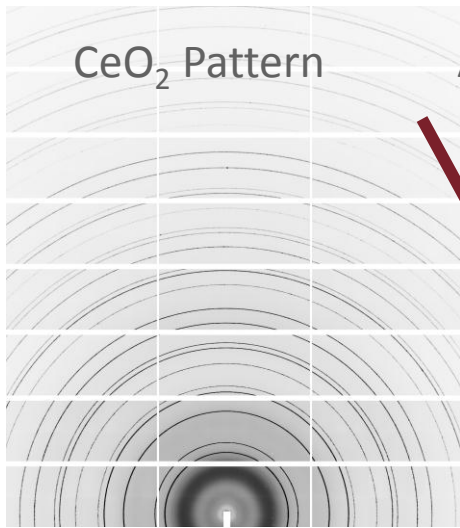


ANL



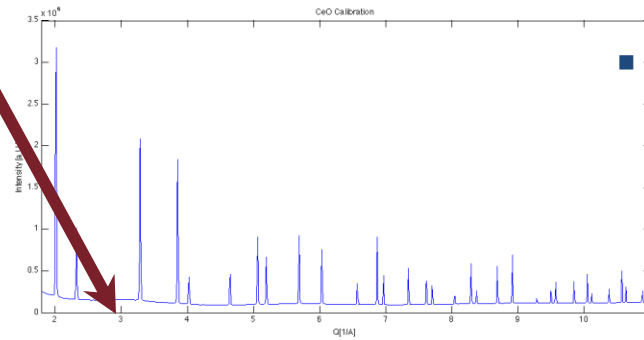
- Experiments take place at BNL/NSLS I and ANL/APS
- Currently no dedicated insitu chamber available
- However: New chamber for BNL in commissioning and transportable evaporator under design

Data-Processing



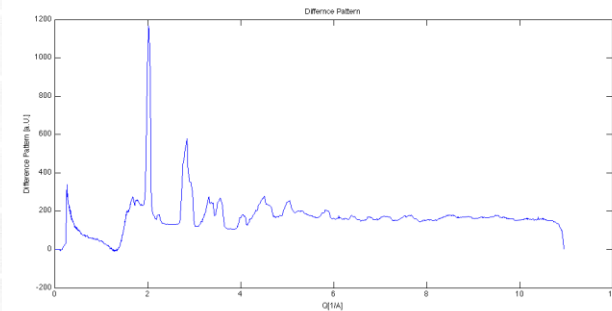
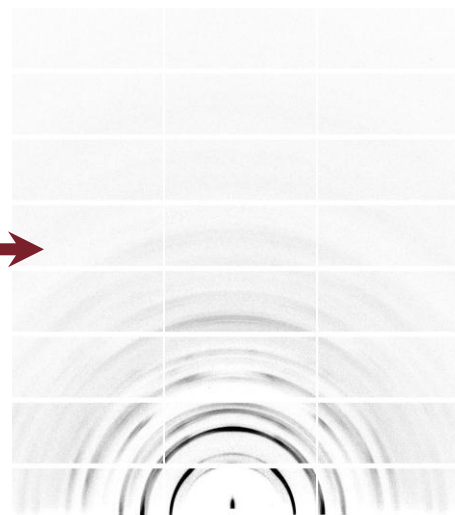
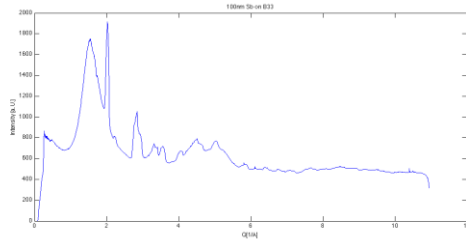
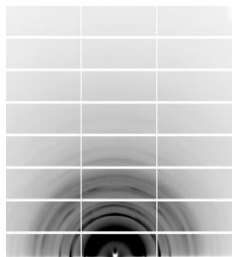
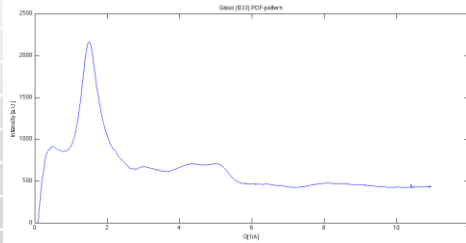
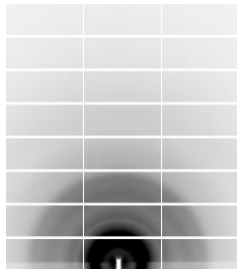
CeO₂ Pattern

Azimuthal Integration and fit of peak positions

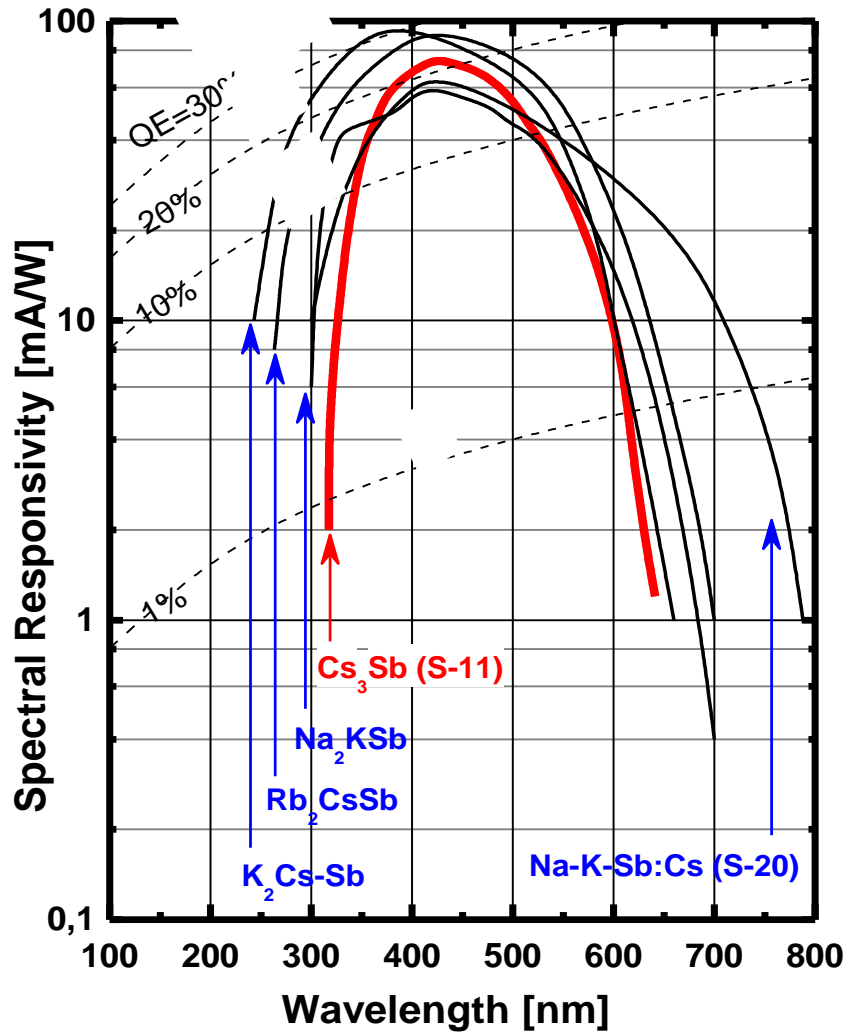


Data-Analysis:

- Calibration with known standard (CeO₂)
- “Empty”-pattern (B33)
- Sb-on B33 pattern
- Result: Difference showing only Sb-film and changes on glass-substrate



A Closer Look to Multi-Alkali Cathodes



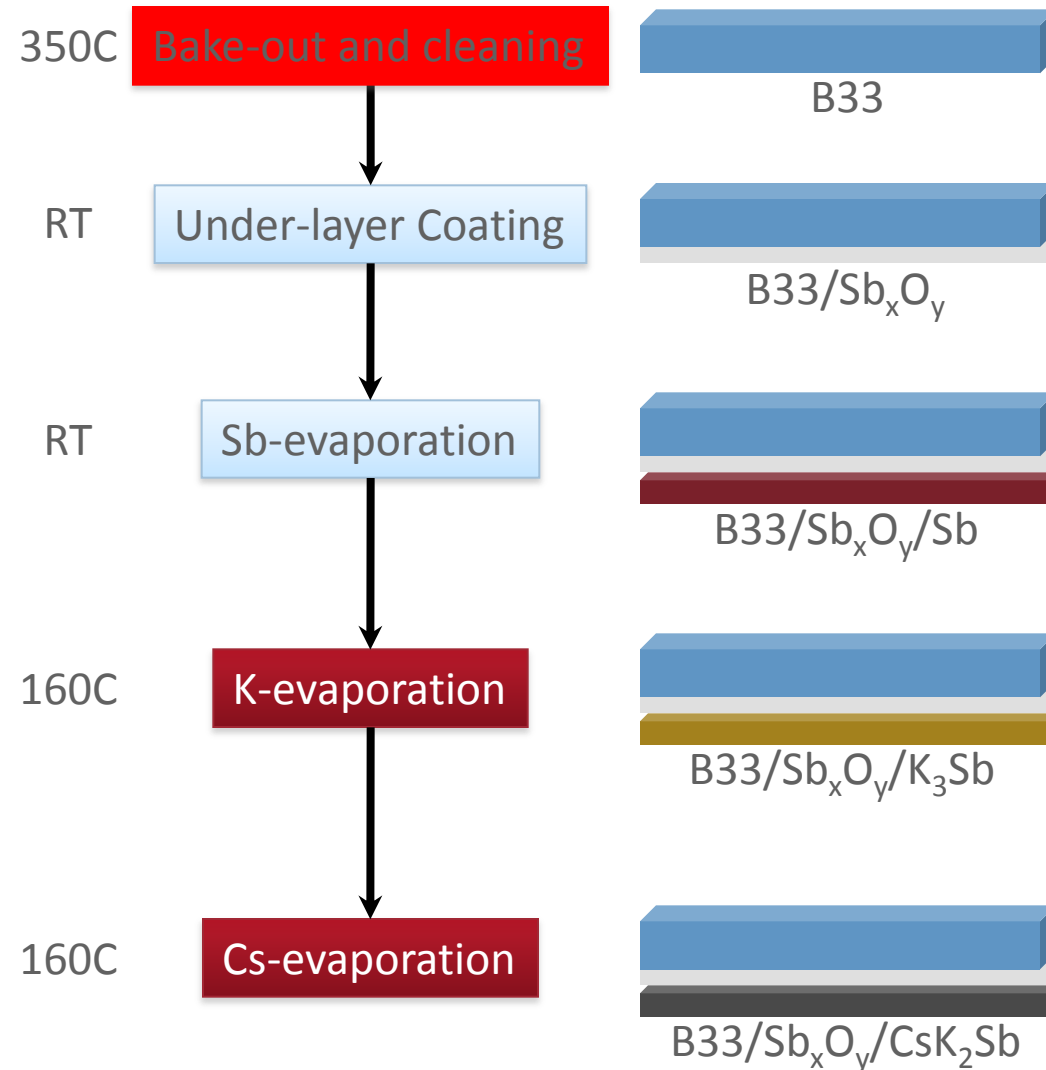
Periodic Table of the Elements

1	2											13	14	15	16	17	18																
1	2											B	C	N	O	F	Ne																
3	4											13	14	15	16	17	18																
3	4											Al	Si	P	S	Cl	Ar																
11	12											27.98	28.086	30.974	32.06	35.45	39.948																
19	20											31	32	33	34	35	36																
19	20											K	Ca	Sc	Ti	V	Cr	Mn	Fe	Co	Ni	Cu	Zn	Ga	Ge	As	Se	Br	Kr				
37	38											39	40	41	42	43	44	45	46	47	48	49	50	51	52	53	54	55	56	57	58	59	
37	38											Rb	Sr	Y	Zr	Nb	Mo	Tc	Ru	Rh	Pd	Ag	Cd	In	Sr	Sb	Te	I	Xe				
55	56											57	72	73	74	75	76	77	78	79	80	81	82	83	84	85	86	87	88	89	90		
55	56											Cs	Ba	*La	Hf	Ta	W	Re	Os	Ir	Pt	Au	Hg	Tl	Pb	Bi	Po	At	Rn				
87	88											89	104	105	106	107	108	109	110														
87	88											Fr	Ra	+Ac	Rf	Ha	106	107	108	109	110												

- Typical compound: SbA_3
- A: (Li), Na, K, Cs
- Various combinations are possible

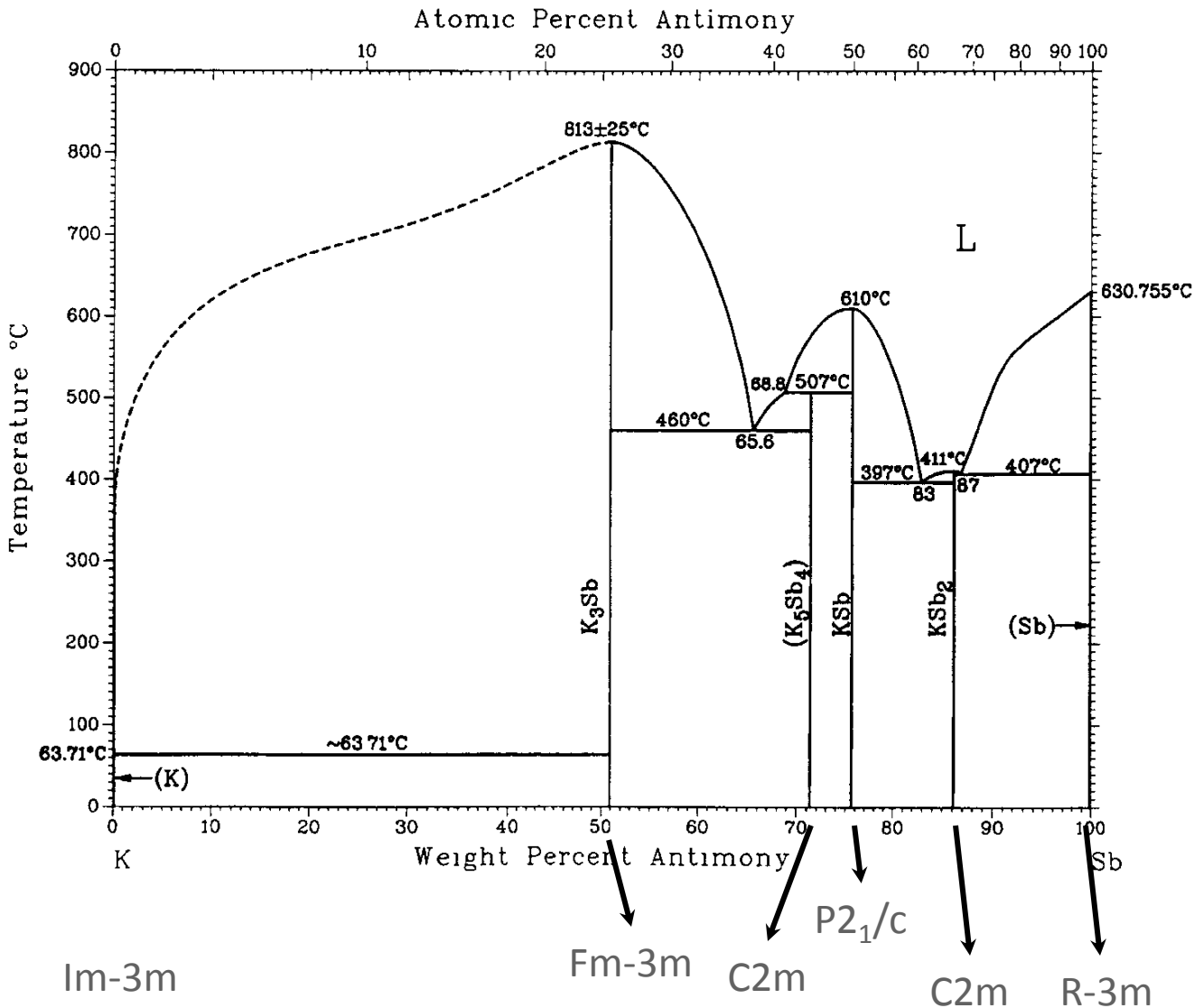
A. Lvashenko

What Can We Learn from the Past?



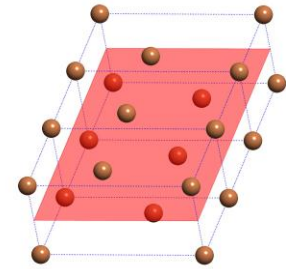
- The cathode of interest: CsK₂Sb
- Recipe from different communities
 - Various recipes are available
 - Recipe includes:
 - Process timing
 - Process temperatures (and ramps)
 - Evaporator design, pump rates, details of materials....
 - Recipe depends on evaporator system
- Groups of recipes
 - Either Co-evaporation or sequential evaporation
 - Interlayer between glass and cathode or none

What Happens on an Atomistic Level?



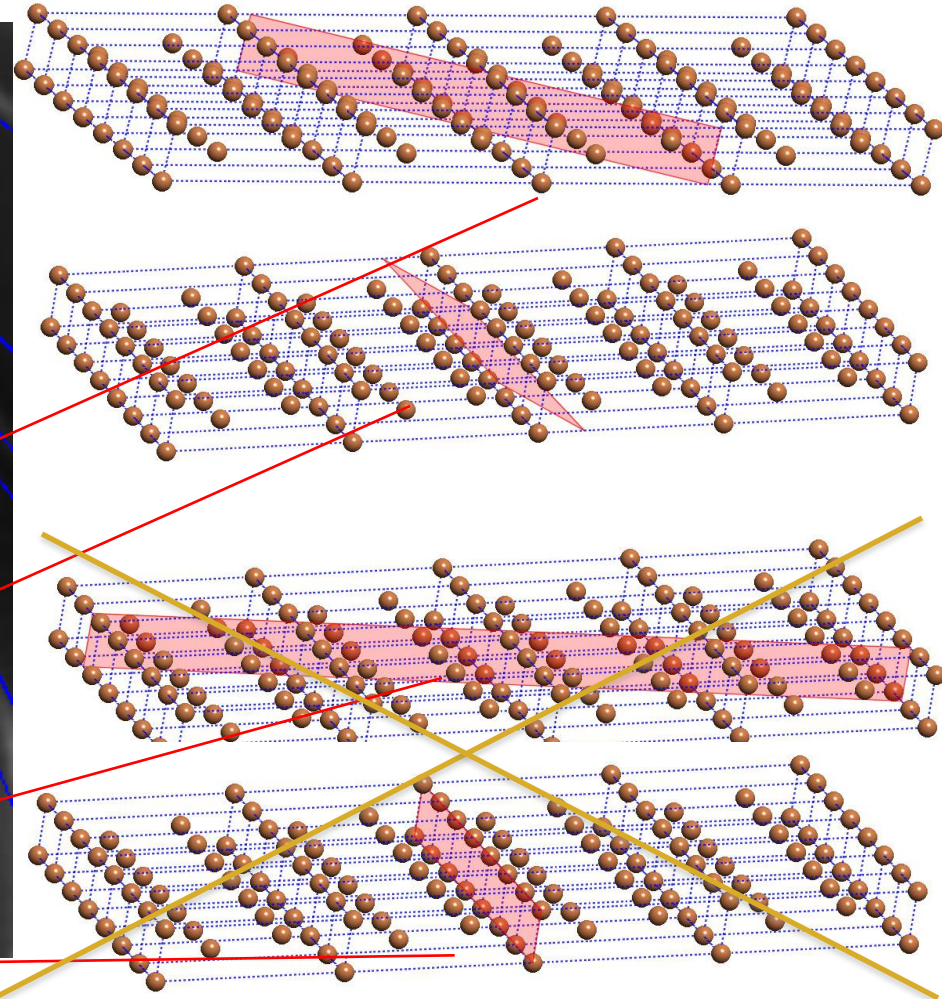
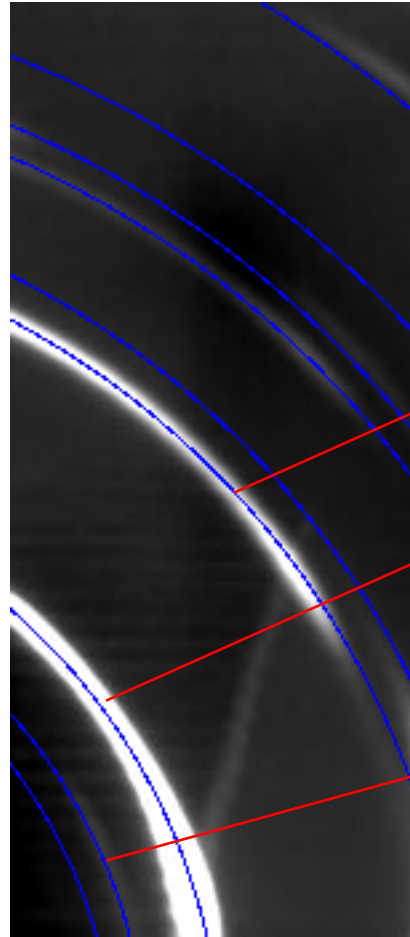
- B33 (substrate)
 - How clean is clean
 - Is there any influence of surface states
- Interlayer
 - Chemical composition
 - Roughness
 - structure
- Conversion of Sb-Metal $\rightarrow K_3Sb$
 - Influence of Sb-Metal structure on final K_3Sb structure?
 - Final structure
 - Final composition
- Conversion of $K_3Sb \rightarrow CsK_2Sb$
 - Same questions as above

Pre-alignment of the Sb-layer



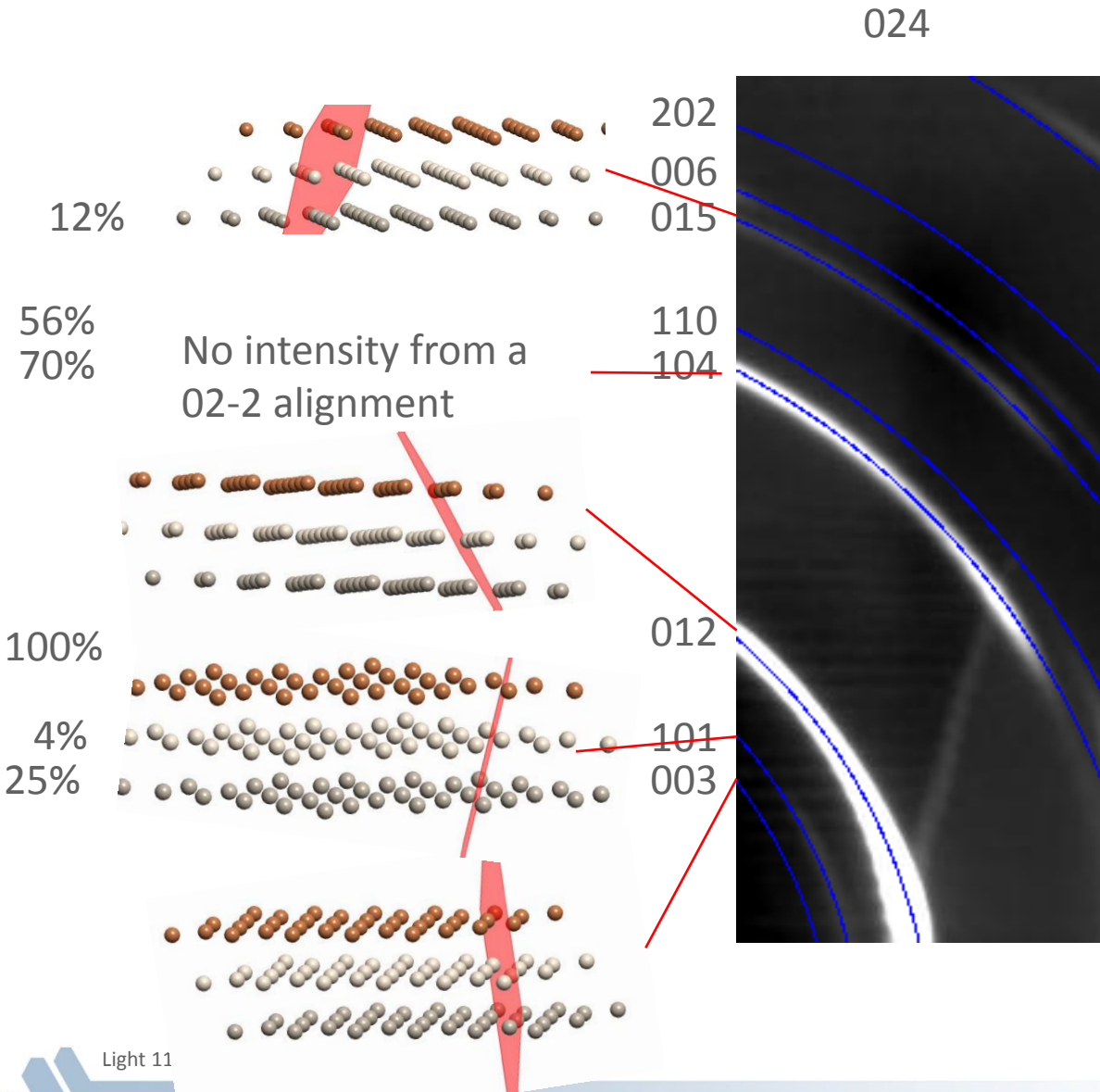
?

2θ	intensity	h k l
46.99	15	0 2 4
41.00	26	2 0 2
38.55	35	0 0 6
37.49	12	0 1 5
33.48	56	1 1 0
32.01	70	1 0 4
23.00	100	0 1 2
20.18	4	1 0 1
19.02	25	0 0 3

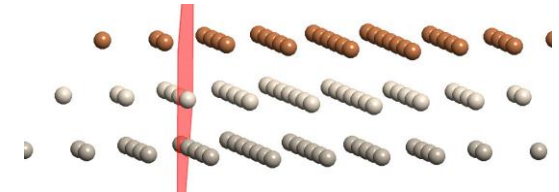


- Preliminary analysis:
Crystallites grow with 010-plane on the substrate

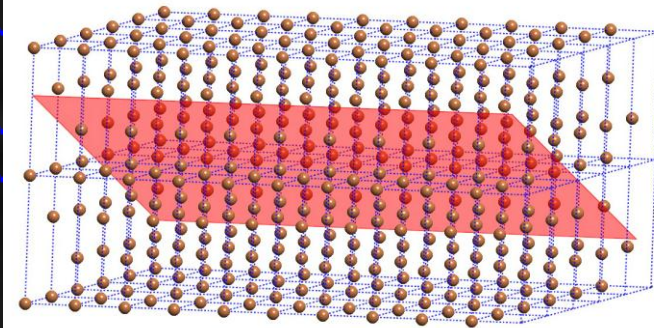
The Sb-Film and the Substrate



104- reflection:



02-2 alignment



001 alignment

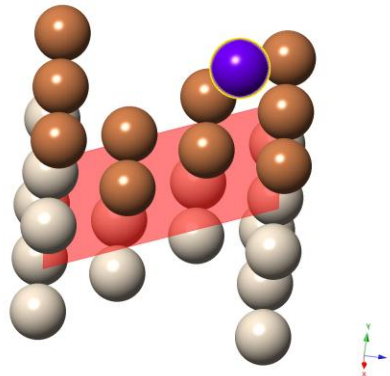
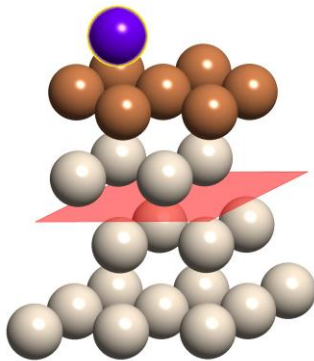
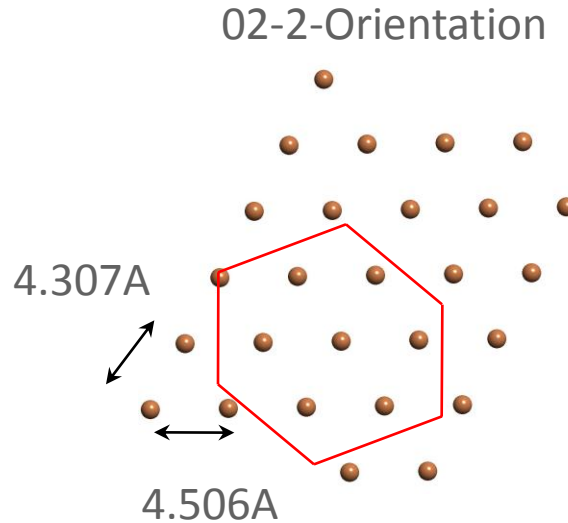
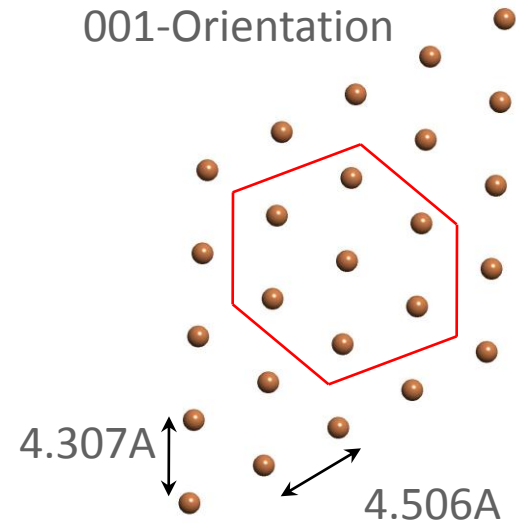
Crystal-interface is most likely a combination of 02-2 and 001 crystallites

Some Properties of the two Crystallite Orientations

First layer between cathode and substrate:

001-Orientation

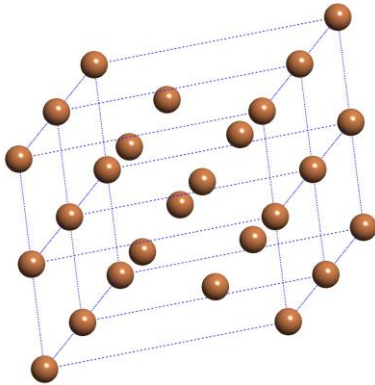
02-2-Orientation



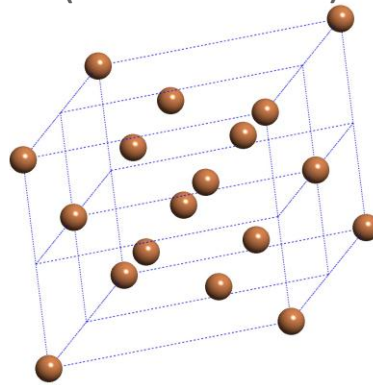
- Both crystallites give similar growth conditions
- Ionic radius of K is larger as the “open” area -> no easy inter-diffusion
- Steps may play a major role for start of inter-diffusion
- Explains initial amorphous growth (after 6nm crystalline)
- In first order:
 - substrate can not influence the growth ratio
 - Two crystallite-types determine grain boundary condition
 - Grain-boundary are important for K-inter-diffusion?

How can you get from Sb-Metal to K_3Sb

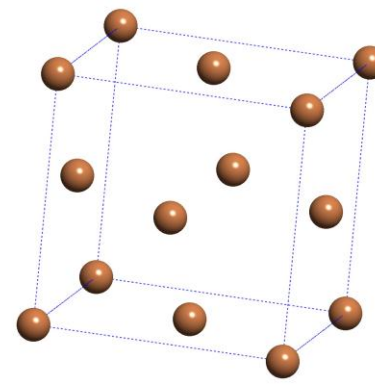
4 unit cells of Sb



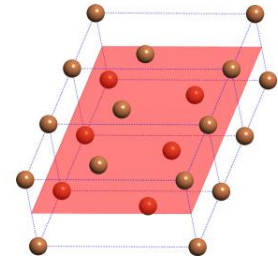
Removing 8 atoms
(two fcc-sides)



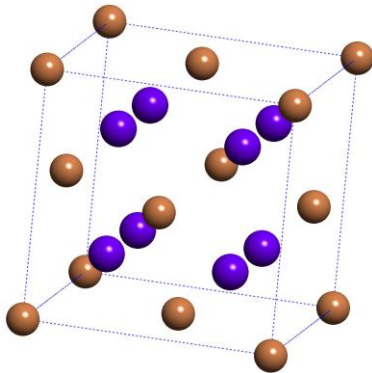
Moving the rest of the atoms
to the FCC side



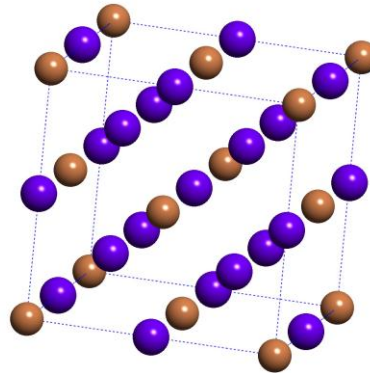
Sb-Metal surface



Filling the inner K sides



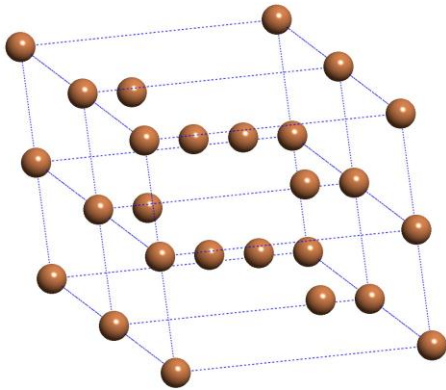
Filling the outer K sides



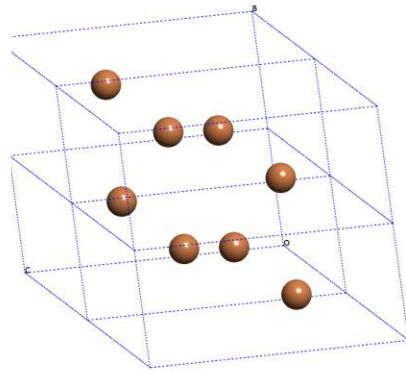
- Many Atoms have to be moved/removed
 - Not clear where they go?
 - Does the film loose Sb atoms during K-Sb reaction?
- Inter diffusion of K will not be possible for all crystal planes!
- Is K-Sb bonding energy the “motor “ of this transition?

How can you get from Sb-Metal to KSb

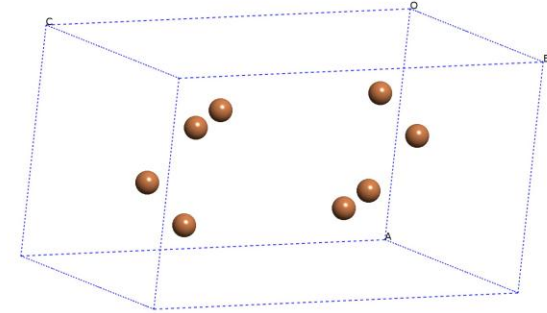
Sb-metal



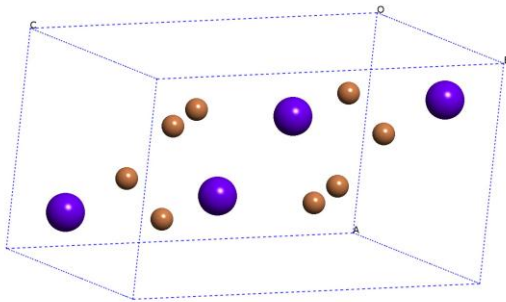
Removing of corner atoms



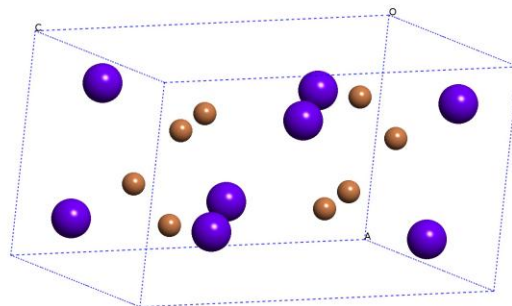
Rearranging Sb-atoms



Filling first K-position



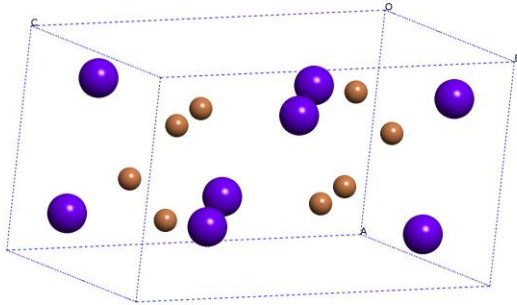
Filling second K-position



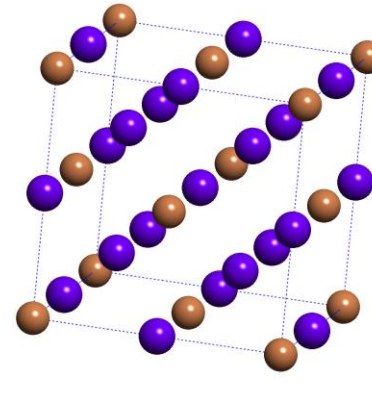
- Fewer Sb-atoms have to be removed
- Strong Sb-Sb bonds (spiral)
- K-cage holds the crystal together

No transition between KSb and K₃Sb?

KSb



K₃Sb



- No Transition between KSb and K₃Sb possible (wrong Sb-positions are occupied) without melting?
- Access K yields to lateral segregation not to a transition
- What drives the initial growth?

Characterization of the Full Cathode Growth

Sample 1

8 nm Sb deposition at 100 C
16 nm K deposition at 100 C
Substrate heating to 300 C
18 nm Cs deposition at 100 C
Substrate heating to 300 C
8 nm Sb deposition at 100 C
24 nm Cs deposition at 100 C
Substrate heating to 300 C

Sample 2

16 nm Sb deposition at 30 C
63 nm K deposition at 100 C
Substrate heating to 300 C
16 nm Sb deposition at 100 C
40 nm Cs deposition at 100 C
Substrate heating to 300 C

Sample	Total Sb	Total K	Total Cs
Sample 1	16nm	16nm	42nm
Sample 2	32nm	63nm	40nm

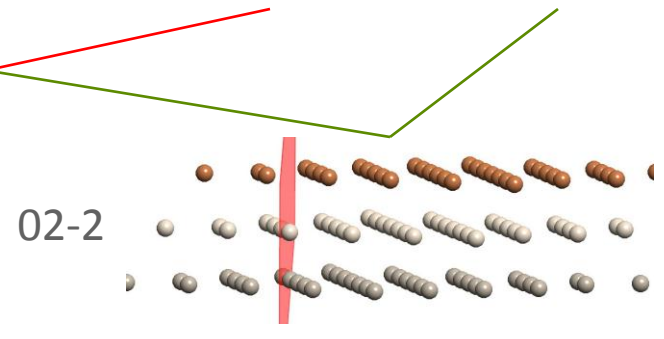
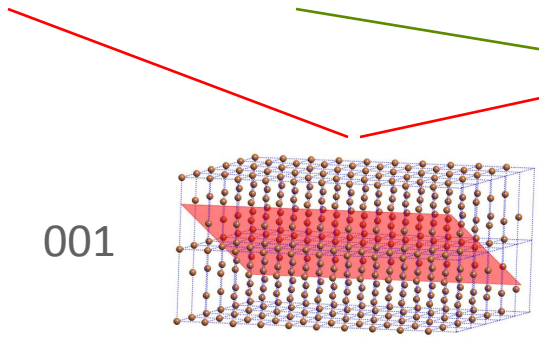
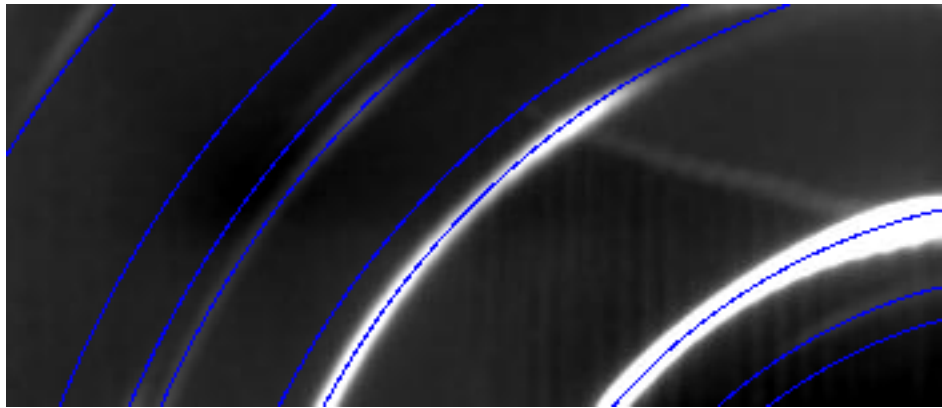
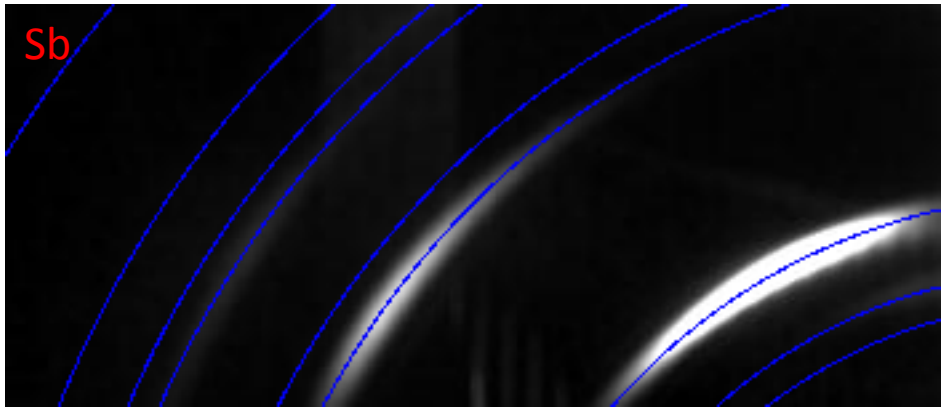
- Growth temperature of Sb-film
- Sequence of growth
- Total thickness

Initial Sb-Film

Thickness	8nm	16nm
Temperature	30C	100C

Sample 1

Sample 2

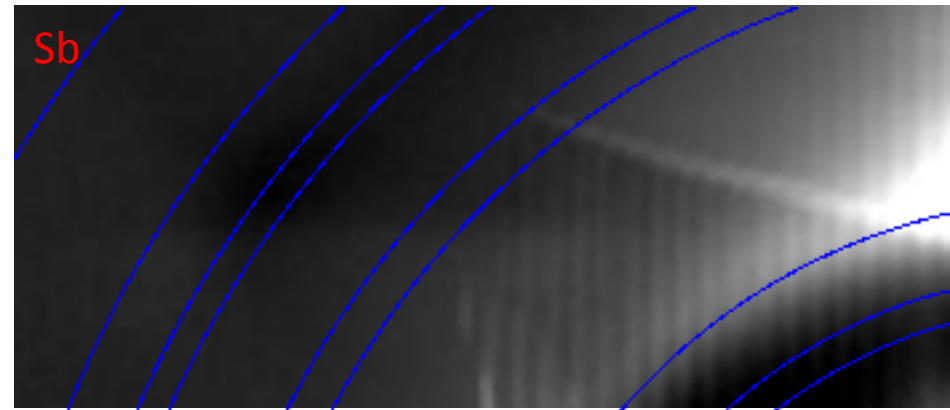
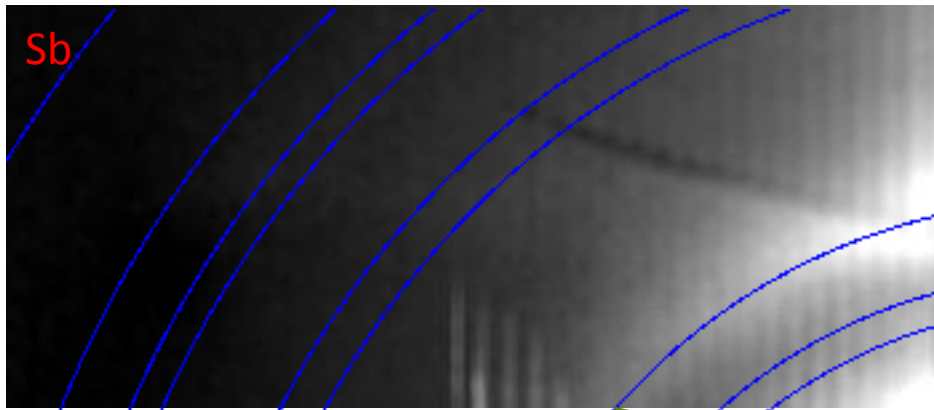


First K-deposition

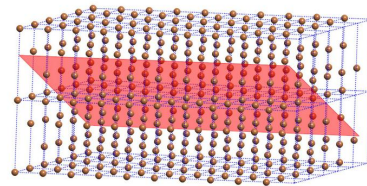
Thickness	Sb 8nm/ K 16nm	Sb 16nm / K 63nm
Temperature	100C	100C

Sample 1

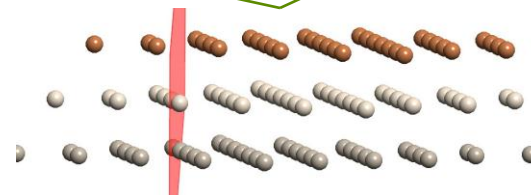
Sample 2



Reacted 001



02-2

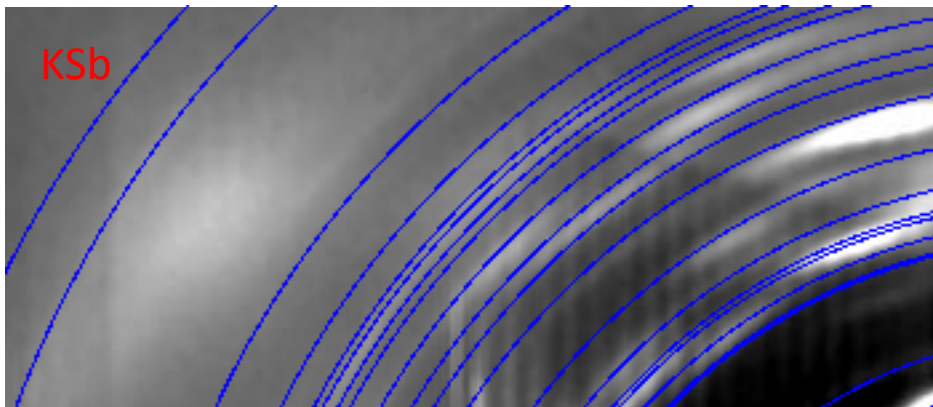
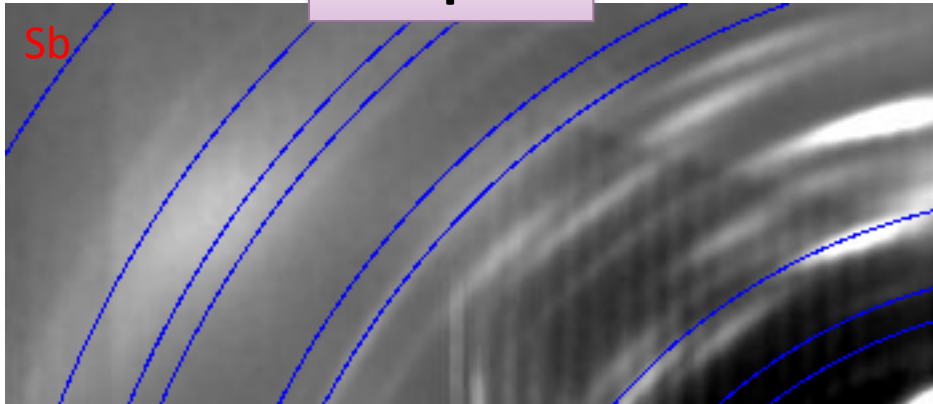


Not reacted?
Strongly strained
A specific
orientation
survived

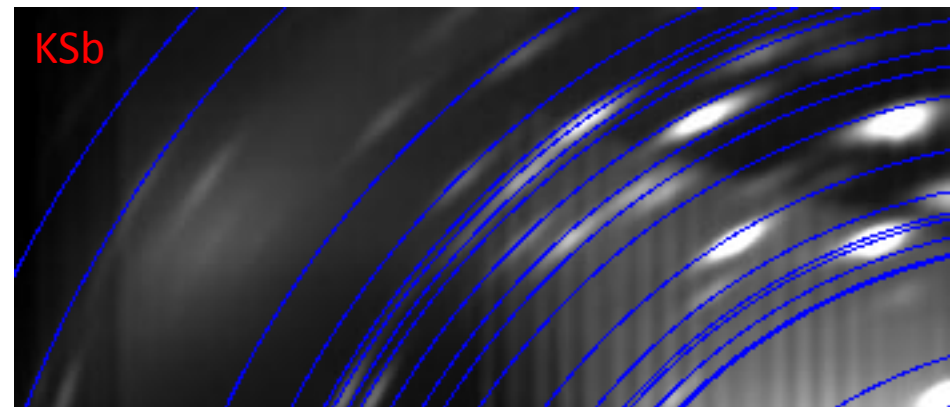
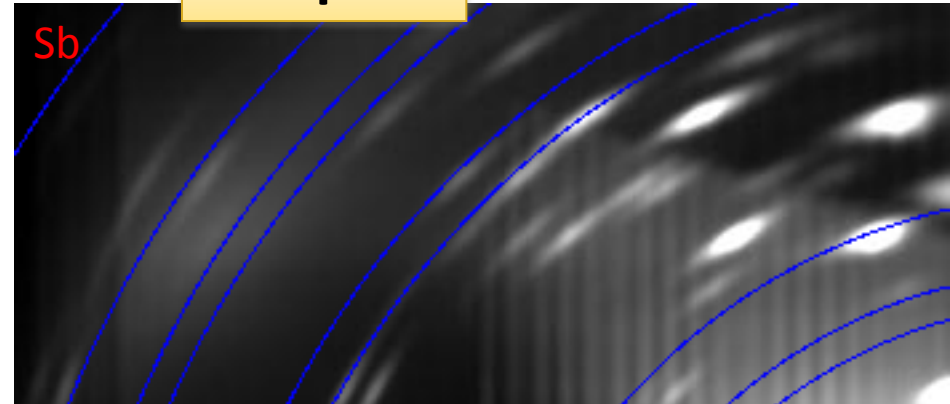
Annealing of KSb-Compound at 300C

Thickness	Sb 8nm/ K 16nm	Sb 16nm / K 63nm
Annealing Temperature	300C	300C

Sample 1



Sample 2

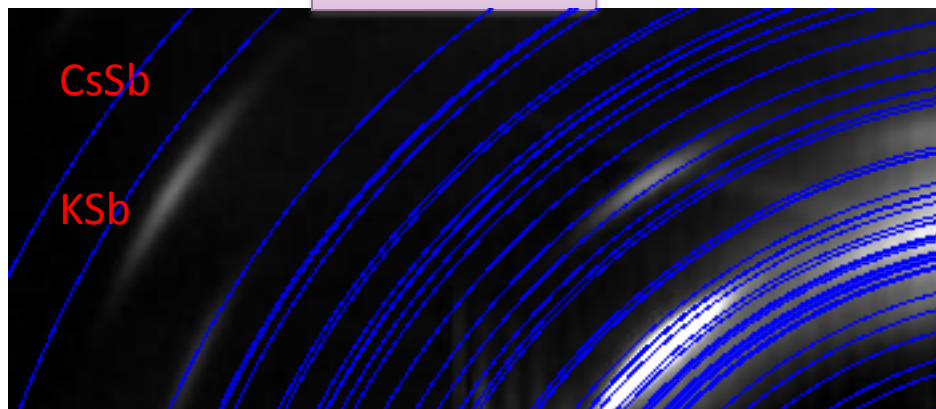


- KSb in both cases (independent from K-thick.); some systematic deviation (strain/vacancies?)
- Very strong texturing for sample 2
- May be Sb-metal phase (001-phase)

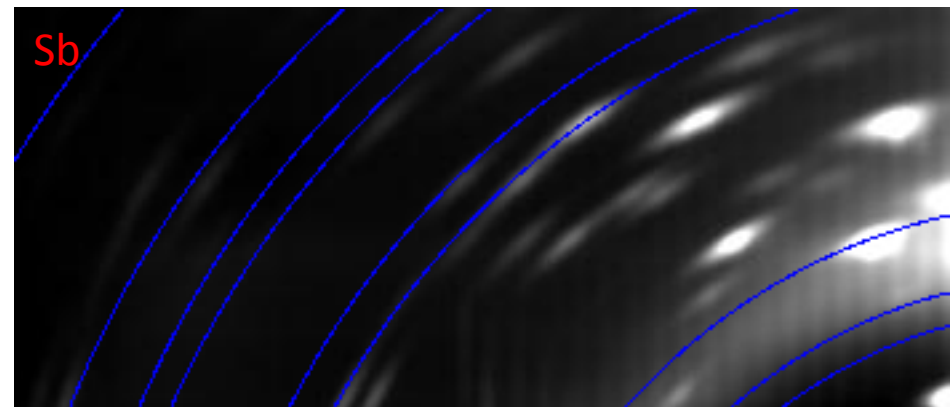
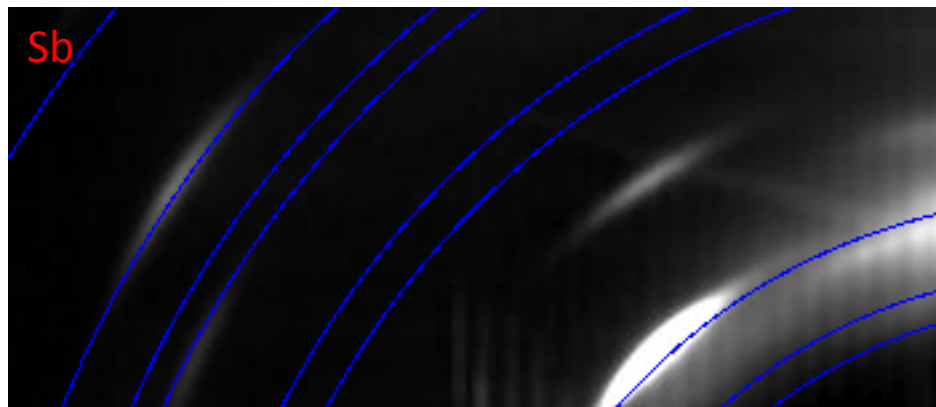
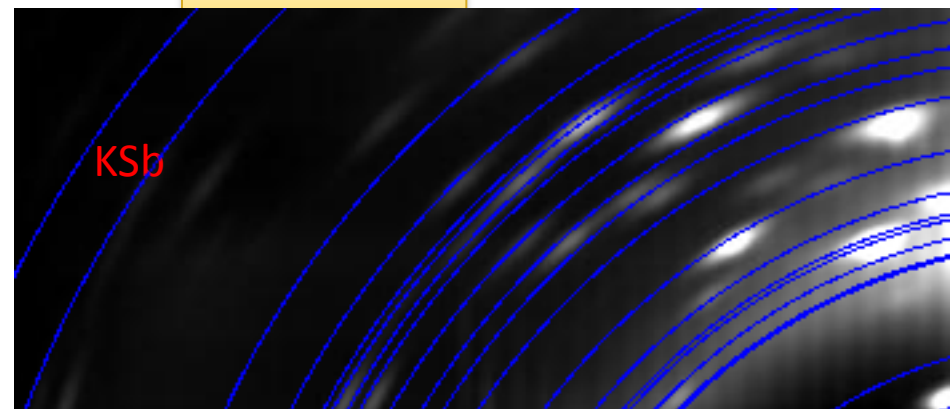
Cs-Deposition

Thickness	Sb 8nm/ K 16nm /18nm	Sb 16nm / K 63nm/ Sb 16nm / 40nm Cs
Annealing Temperature	100C	100C

Sample 1



Sample 2

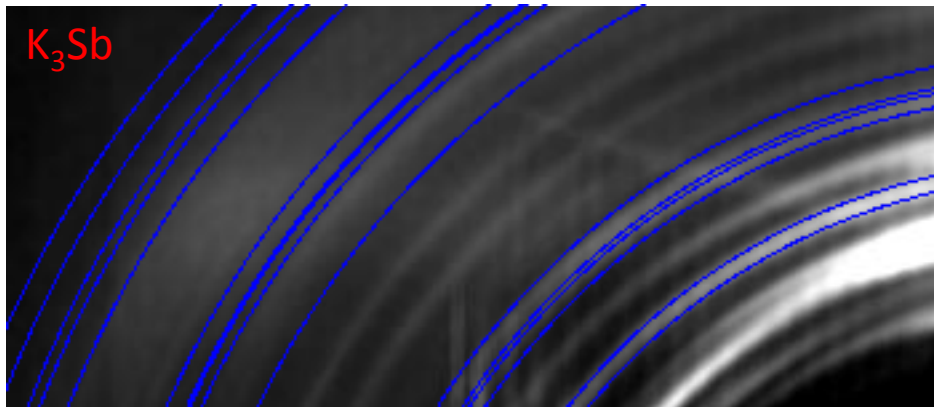
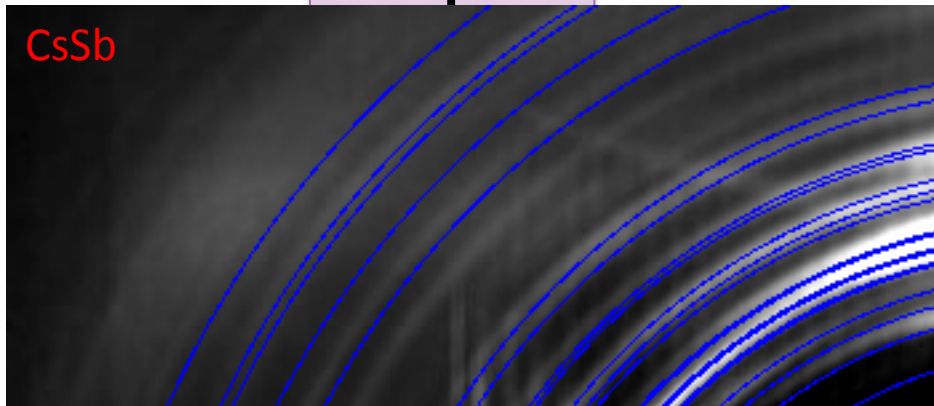


- Some metallic Sb left in both cases
- No crystalline phase of alkali-Sb for sample 1
- KSb phase visible for Sample 2

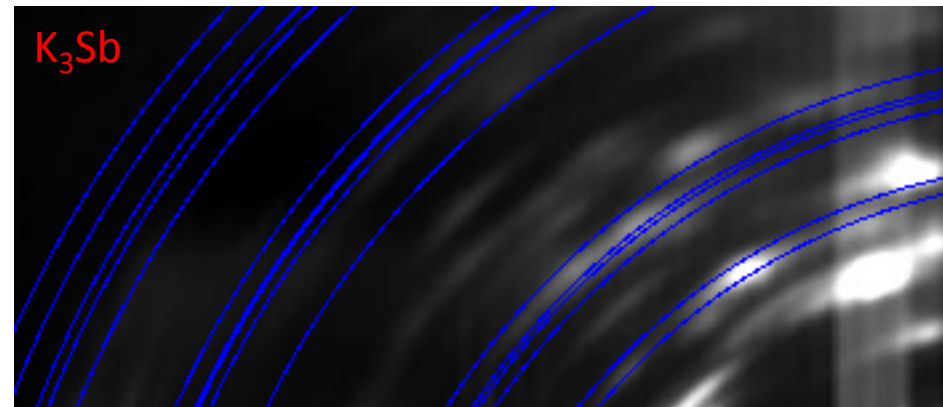
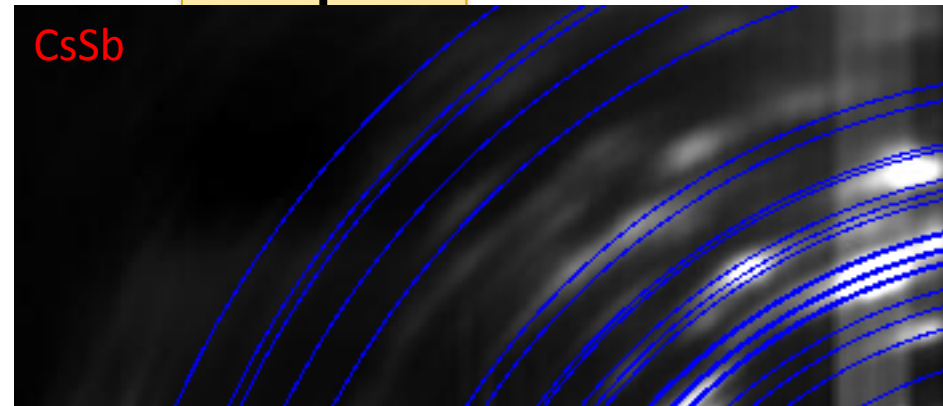
Annealing of CsKsSb-Compound at 300C

Thickness	Sb 8nm/ K 16nm /18nm	Sb 16nm / K 63nm/ Sb 16nm / 40nm Cs
Annealing Temperature	300C	300C

Sample 1



Sample 2

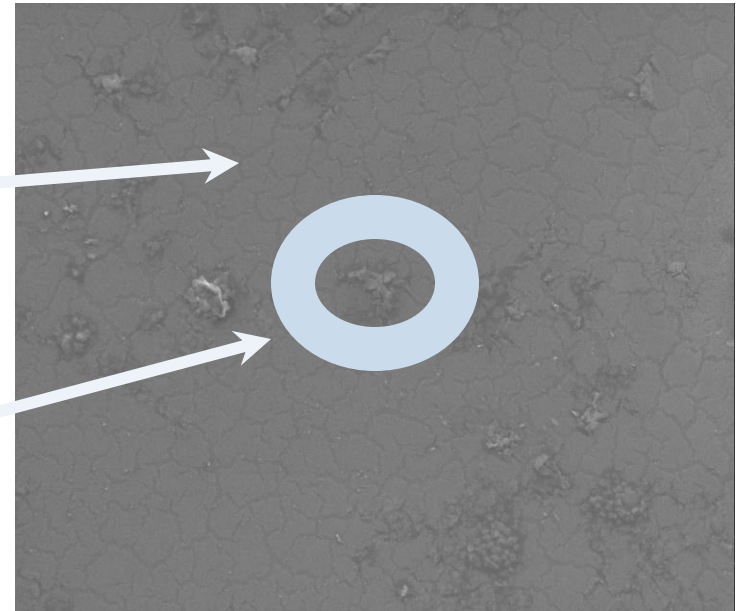


- In both cases mixture of AlSb (Al=Cs/K)
- Unlikely a Al₃K-phase! (Al=Cs/K)

Summary of In-situ Growth Experiment

Sb K Cs on Si X21 Oct 2011 Samp 3 1 Date:10/5/2011 4:31:31 PM HV:15.0kV Puls
th.:17.27kcps Center Average

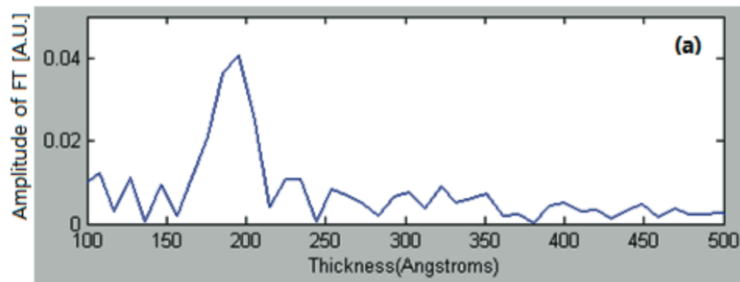
El	AN	Series	unn. C [wt.%]	norm. C [wt.%]	Atom. C [at.%]	Error [%]
C	6	K-series	0.54	0.56	1.35	0.9
O	8	K-series	3.69	3.85	6.90	1.1
Si	14	K-series	84.15	87.79	89.71	3.5
K	19	K-series	0.52	0.54	0.40	0.1
Sb	51	L-series	3.88	4.05	0.96	0.6
Cs	55	L-series	3.08	3.21	0.69	0.3
Total:			95.86	100.00	100.00	



- Observations: Very K-rich (K-metal?)
 - Sb-metal film growth often strongly textured
 - K-evaporation onto of Sb-metal yield to an amorphous material or glass (no long range order)
 - Formation of islands are unlikely since this would favorite crystalline phases which cannot be detected!
 - K-Sb mixture crystallizes at 300C (dynamics, activation energies are currently not known but can be extracted from existing data set)
 - Crystallized K-Sb film is mainly KSb with strong texturing (orientation and crystal size can be concluded from existing data set)
 - Cs behaves very similar to K
 - Produced cathode was not homogeneous: largely a CsSb-phase and a crystalline non identified CsKSb-phase

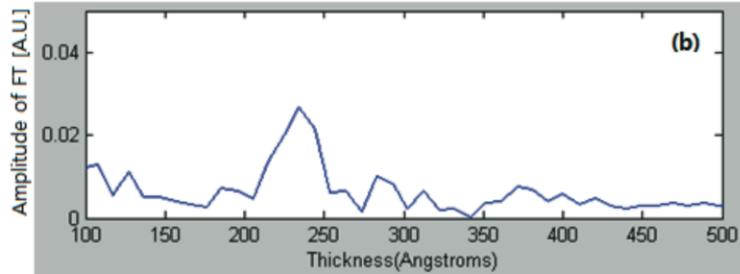
The Transition from Sb-Film to K_3Sb -film

Surface Roughness during the Processing



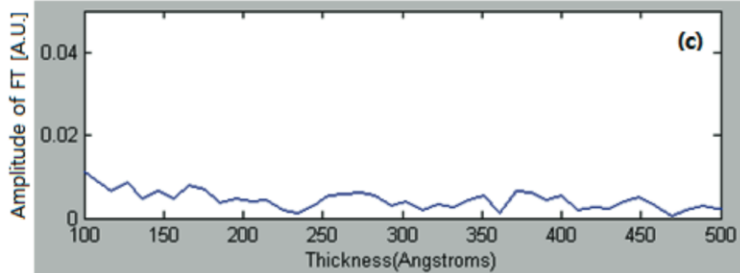
Sb-Metal

- Nice smooth film with 19nm thickness
- Height distribution ~ 3 nm



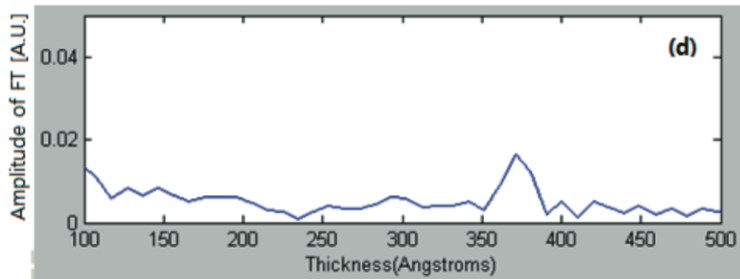
K-evaporation started

- Decrease of peak height indicates fraction of surface don't contribute to signal
- Height distribution $\sim 5-7$ nm
- No double layer structure



K-evaporation ended

- No reflectivity signal detectable
- Very rough!



heating

- Reflectivity signal comes back
- Not all surface has recovered
- Goes ahead with crystallization!

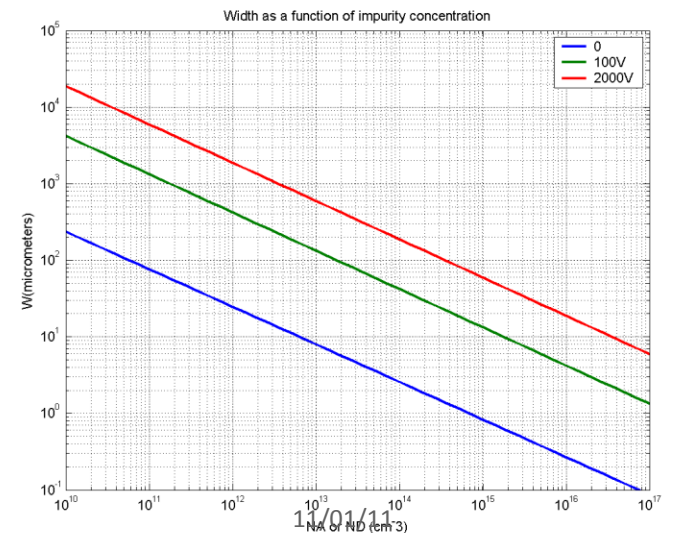
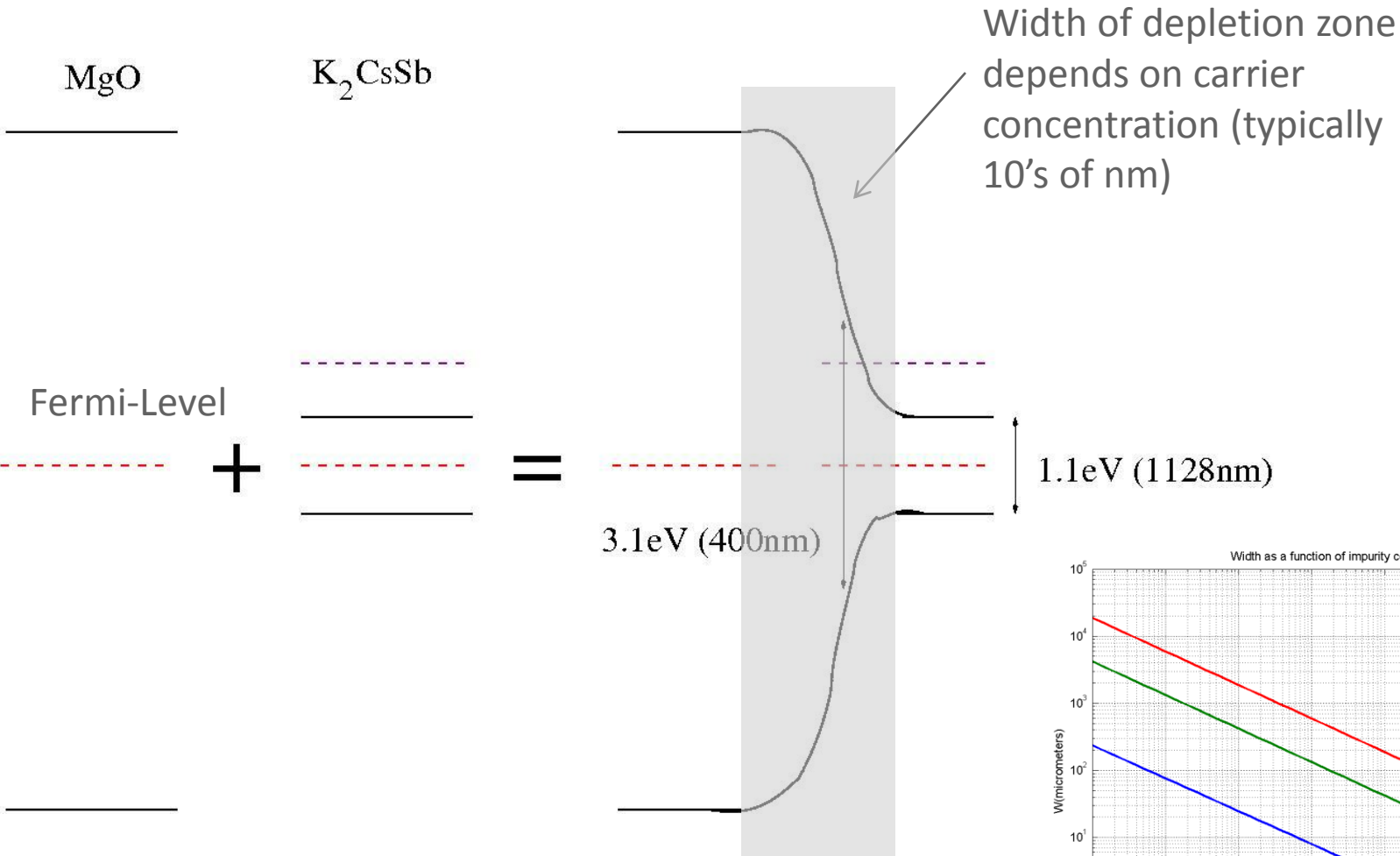
Influence of Interface Layer

- Commonly used materials:

Material	Crystal group	Lattice parameter	Match with K_3Sb	Band gap
Sb_2O_3	Fd-3m	$a=11.152\text{\AA}$	yes	3.7-3.9eV
Sb_2O_4	Fd-3m	$a=10.26\text{\AA}$	yes	?
MgO	Fm-3m	$a=4.2117\text{\AA}$	excellent	4.7-7.8eV
BeO	$P6_3mc$	$a=2.698\text{\AA}$ $c=4.3772\text{\AA}$	no	10.7eV
K_3Sb	F m -3 m	$a=8.493$		1.4eV
CsK_2Sb	F m -3 m	$a=8.61$		1.0-1.2eV

BeO is used to produce super-alkali cathodes!

Combining Wide-Band-Gap Materials with Alkali Systems



The Next Steps

- Instrumentation:
 - Development of miniature evaporator system with defined growth conditions (high q-range, easy to transport, can be implemented in various beamlines)
 - Data-quality improvement: calibration standard & background reduction
- Data-analysis, simulation, & theory:
 - Automatic data analysis using script languages
 - Quantitative analysis of texture information
 - Peak-width simulation based on strain, size and defect-structure
 - Data base for known compounds (alkali-Sb and oxides/fluorids)
 - Calculation of potential surface for Alkali inter diffusion (at least important areas)
- Program:
 - Influence of Oxide layer on growth and band bending
 - Understanding of KSb versus K_3Sb growth

Conclusion

- In-situ X-ray diffraction and reflectivity was applied and provides:
 - Compound composition during the processing
 - Structural information on crystallinity, size and orientation of crystals
 - Temporal evolution of these parameters
- Results of the presented experiment:
 - Alkali-evaporation at 100C substrate temperature yields to amorphous or glassy material
 - No transversal but lateral segregation is observed.
 - Crystallization can be achieved at 300C heating (necessary time can be extracted from data)
 - Grown cathode is more of the CsSb and some non-identified CsKSb-compound (not CsK₂Sb)
 - Crystallinity (and texture) of the final film is independent from the Sb-structure but may depend on the KSb-crystallinity and the influence of the substrate layer?
- Next goals
 - Improve in-situ experiment so that many cathode recipes can be investigated.
 - Influence of the substrate on the crystallization process of the Alkali compound
 - Determination of activation energies and rate constants of the crystallization process (for the different compounds).